

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

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Application of

Jun OSANAI et al.

Serial No. 09/944,365

Filed: August 31, 2001

For: COMPLEMENTARY MOS SEMICONDUCTOR DEVICE AND

METHOD OF MANUFACTURING

THE SAME

: Group Art Unit - 2811

: Examiner - Thien F. Tran

Docket No. S004-4393

MS FEE AMENDMENT COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, VA 22313-1450

SUPPLEMENTAL RESPONSE

S I R:

In further response to the Office Action mailed March 3, 2003, applicants further amend their application as follows:

IN THE SPECIFICATION:

Please replace the paragraph beginning at page 91, line 3, with the following rewritten paragraph:

-- The formation of the P+resistor 116 and the N+resistor 117 is attained by simultaneously doping the

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